

Sheikh Ziaur Rahaman

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/7464013/publications.pdf>

Version: 2024-02-01

28
papers

664
citations

567281

15
h-index

580821

25
g-index

28
all docs

28
docs citations

28
times ranked

922
citing authors

#	ARTICLE	IF	CITATIONS
1	An 8kb spin-orbit-torque magnetic random-access memory. , 2021, , .		6
2	Size-Dependent Switching Properties of Spin-Orbit Torque MRAM With Manufacturing-Friendly 8-Inch Wafer-Level Uniformity. IEEE Journal of the Electron Devices Society, 2020, 8, 163-169.	2.1	12
3	Pulse-Width and Temperature Effect on the Switching Behavior of an Etch-Stop-on-MgO-Barrier Spin-Orbit Torque MRAM Cell. IEEE Electron Device Letters, 2018, 39, 1306-1309.	3.9	29
4	The Role of Ti Buffer Layer Thickness on the Resistive Switching Properties of Hafnium Oxide-Based Resistive Switching Memories. Langmuir, 2017, 33, 4654-4665.	3.5	51
5	Understanding of multi-level resistive switching mechanism in GeOx through redox reaction in H2O2/sarcosine prostate cancer biomarker detection. Scientific Reports, 2017, 7, 11240.	3.3	27
6	Scalability and reliability issues of Ti/HfO _x -based 1T1R bipolar RRAM: Occurrence, mitigation, and solution. Applied Physics Letters, 2017, 110, .	3.3	19
7	Occurrence and solution to overcome 1 st RESET resistance pinning effect in Ti/HfO ₂ /x ₂ /y ₂ based RRAM for low power nonvolatile memory applications. , 2017, , .		0
8	Retention Model of TaO/HfO _x and TaO/AlO _x RRAM with Self-Rectifying Switch Characteristics. Nanoscale Research Letters, 2017, 12, 407.	5.7	16
9	Effect of Ti buffer layer on HfOx-based bipolar and complementary resistive switching for future memory applications. , 2016, , .		1
10	Temperature-Dependent Non-linear Resistive Switching Characteristics and Mechanism Using a New W/WO ₃ /WO _x /W Structure. Nanoscale Research Letters, 2016, 11, 389.	5.7	43
11	Resistive and New Optical Switching Memory Characteristics Using Thermally Grown Ge _{0.2} Se _{0.8} Film in Cu/GeSex/W Structure. Nanoscale Research Letters, 2015, 10, 392.	5.7	10
12	Conductive-bridging random access memory: challenges and opportunity for 3D architecture. Nanoscale Research Letters, 2015, 10, 188.	5.7	76
13	Resistive switching memory characteristics of Ge/GeO _x nanowires and evidence of oxygen ion migration. Nanoscale Research Letters, 2013, 8, 220.	5.7	40
14	Comparison of resistive switching characteristics using copper and aluminum electrodes on GeOx/W cross-point memories. Nanoscale Research Letters, 2013, 8, 509.	5.7	10
15	Ti/HfO ₂ Based RRAM Operation Voltage Scaling for Embedded Memory. ECS Transactions, 2013, 52, 39-44.	0.5	1
16	Bipolar Resistive Switching Memory Characteristics Using Al/Cu/GeO _x /W Memristor. ECS Transactions, 2012, 45, 257-261.	0.5	15
17	Record Resistance Ratio and Bipolar/Unipolar Resistive Switching Characteristics of Memory Device Using Germanium Oxide Solid Electrolyte. Japanese Journal of Applied Physics, 2012, 51, 04DD11.	1.5	7
18	Excellent Uniformity and Multilevel Operation in Formation-Free Low Power Resistive Switching Memory Using IrO _x /AlO _x /W Cross-Point. Japanese Journal of Applied Physics, 2012, 51, 04DD10.	1.5	9

#	ARTICLE	IF	CITATIONS
19	Excellent resistive memory characteristics and switching mechanism using a Ti nanolayer at the Cu/TaOx interface. <i>Nanoscale Research Letters</i> , 2012, 7, 345.	5.7	78
20	Enhanced nanoscale resistive switching memory characteristics and switching mechanism using high-Ge-content Ge _{0.5} Se _{0.5} solid electrolyte. <i>Nanoscale Research Letters</i> , 2012, 7, 614.	5.7	29
21	Excellent Uniformity and Multilevel Operation in Formation-Free Low Power Resistive Switching Memory Using IrO _x /AlO _x /W Cross-Point. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 04DD10.	1.5	16
22	Record Resistance Ratio and Bipolar/Unipolar Resistive Switching Characteristics of Memory Device Using Germanium Oxide Solid Electrolyte. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 04DD11.	1.5	3
23	High- $\hat{\rho}$ Al ₂ O ₃ /WO _x Bilayer Dielectrics for Low-Power Resistive Switching Memory Applications. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 10PH01.	1.5	21
24	Improved Resistive Switching Memory Characteristics Using Core-Shell IrO _x Nano-Dots in Al ₂ O ₃ /WO _x Bilayer Structure. <i>Journal of the Electrochemical Society</i> , 2011, 159, H177-H182.	2.9	34
25	High- $\hat{\rho}$ Al ₂ O ₃ /WO _x Bilayer Dielectrics for Low-Power Resistive Switching Memory Applications. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 10PH01.	1.5	13
26	Low power resistive switching memory using Cu metallic filament in Ge _{0.2} Se _{0.8} solid-electrolyte. <i>Microelectronics Reliability</i> , 2010, 50, 643-646.	1.7	12
27	Bipolar Resistive Switching Memory Using Cu Metallic Filament in Ge _{0.4} Se _{0.6} Solid Electrolyte. <i>Electrochemical and Solid-State Letters</i> , 2010, 13, H159.	2.2	57
28	Nanoscale (EOT = 5.6 nm) nonvolatile memory characteristics using n-Si/SiO ₂ /HfAlO nanocrystal/Al ₂ O ₃ /Ptcapacitors. <i>Nanotechnology</i> , 2008, 19, 435202.	2.6	29